# 10920 CS 512200 VLSI Design for Manufacturability

## **Final Project**

### 109062630 鄭傑予

#### How to compile and execute:

```
--How to Compile

In this directory, enter the following command:

$ make

It will generate the executable file "Hybrid_Lithography" in "Project/bin/".

If you want to remove it and all .o files, please enter the following command:

$ make clean

--How to Run

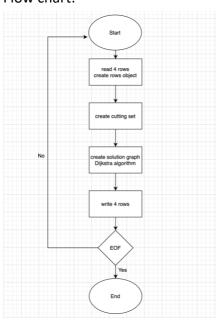
In this directory, enter the following command:

Usage: ../bin/<exe> dis <out file> <out file>
e.g.:

$ ../bin/Hybrid_Lithography 0.064 ../testcase/M0.out ../output/M0_0064.out
```

### Algorithm flow and explanation:

#### Flow chart:



#### Explanation:

由於一開始沒有想到要平行,所以我是一個一個 row 作處理,並且在 enumerate solution 上面是用暴力解,造成後來即使用四核心平行,效能比起 sequential 執行並沒有明顯改善。

但在 ebeam 數量方面,我實做上課教的 TPL 演算法,並用 Dijkstra 找最短路 徑,所以如果程式跑完得到的會是 optimal 的 coloring solution。

	M0.out	aes.out
0.064	0	0
0.128	4981	3096